

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments	Error Defini tion	Errors
1	BRS	L1	9	5,996,595	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/18 14:55			0
2	BRS	L2	60	5,678,116	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/18 15:38			0
3	BRS	L3	141	((degas\$5 or degassification) with (water or "H.sub.2 O")) same (ozone or "O.sub.3")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/18 15:40			0
4	BRS	L4	100	3 and @pd<=20010627	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/18 19:58			0
5	BRS	L5	39	clean\$3 with (wafer or substrate) with (chelate\$3 and surfactant)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/18 16:44			0
6	BRS	L6	30	(after adj2 clean\$3) same ((rins\$3 with (wafer or substrate)) with ((water or "H.sub.O") and (oxidant or oxidiz\$3 or "H.sub.2 O.sub.2" or peroxide)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/18 16:45			0
7	BRS	L7	1	5 and 6	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/18 16:44			0
8	BRS	L8	23	5 and rins\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/18 17:06			0
9	BRS	L9	430	(etch\$3 with (substrate or wafer) with (HF or hydrofluoric)) same (("after" or "immediately") with (clean\$ or rins\$3 or neutral\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/18 17:09			0

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments	Error Definition	Errors
10	BRS	L10	222	9 and @pd<=20010627	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/18 18:00			0
11	IS&R	L11	0	("desferriferrioxaminB" same (wafer or substrate)).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/18 18:01			0
12	IS&R	L12	0	("desferriferrioxaminB" same (wafer or substrate)).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/18 18:02			0
13	BRS	L13	1	"desferriferrioxamin B" same (wafer or substrate)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/18 19:57			0
14	BRS	L14	1	BAMTH same (wafer or substrate)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/18 18:05			0
15	BRS	L15	2	"20020102852"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/18 18:04			0
16	BRS	L16	3	("N,N,N-tris[2-(N-hydroxycarbonyl)ethyl]-1,3,5-benzenetricarboxamide" or "BAMTPH") same (wafer or substrate)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/18 19:04			0
17	BRS	L17	4	"molybdic" same (wafer or substrate) same (clean\$3 or etch\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/18 19:05			0
18	BRS	L18	552	(N,N-Bis(2-hydroxyphenyl)ethylenediamine diacetic or HPED) same (wafer or substrate)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/18 20:00			0

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments	Error Defini tion	Errors
19	BRS	L19	99	(N,N-Bis(2-hydroxyphenyl)ethylenediiminodiacetic or HPED) same (wafer or substrate) same (clean\$3 or etch\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/18 19:58			0
20	BRS	L20	28	19 and @pd<=20010627	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/18 19:58			0
21	BRS	L21	2	("N,N-Bis(2-hydroxyphenyl)ethylenediiminodiacetic" or HPED) same (wafer or substrate)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/18 20:00			0